290. PTB-Seminar
VUV and EUV Metrology

PTB Berlin
Abbestr. 2-12
10587 Berlin
Hermann-von-Helmholtz Building

Day 1: Thursday 05.11.2015

9:00	**Registration & Poster Setup**

Time	Speaker	Title	Institute/ Company
10:00	F. Scholze	**Opening and Overview of PTB Activities in VUV and EUV Metrology**	PTB
		Session I: EUVL	
10:20	V. Banine	EUV lithography now	ASML
10:40	H. Enkisch	Overview of EUV Lithography at Carl Zeiss SMT: status and trends in optical coatings	CZ SMT
11:00	A. Ullrich	Recent developments in EUV photomask metrology	AMTC
11:20	Y. Ekinci	Scanning coherent diffraction imaging techniques for EUV photomask metrology	PSI
11:40	P. Naujok	Beyond-EUV multilayer coatings for next generation lithography	IOF
12:00		**Lunch**	
13:00		**Poster Session**	
		Session II: Sources & Instrumentation for EUV	
14:20	A. Meseck	Accelerator based EUV Sources	HZB
14:40	T. Mey	Beam diagnostics at EUV wavelengths	LLG
15:00	J. Vieker	Compact discharge based EUV Source for metrology and inspection	ILT
15:20	L. Juschkin	Application of lens-less imaging techniques for nano-scale microscopy employing plasma-based EUV source	RWTH
15:40	U. Kleineberg	Cr/Sc ML mirrors for isolated attosecond pulses	LMU
16:00		**Coffee Break**	
		Session III: Space instrumentation	
16:40	U. Arp	Improved Ultraviolet Metrology Capabilities at SURF III	NIST
17:00	R. Schäfer	Absolute UV/EUV detection based on ionization chamber measurements	IPM
17:20	M. Caldwell	VUV calibration of the space-flight solar instrument SPICE at MLS	RAL
17:40	S. Gissot	EUV characterization of (P43/P46) phosphor coated FSI CMOS image sensors for solar observations	ROB
18:00			
19:00		**Get Together, Dinner Buffet**	
22:00		**End of Day 1**	